

EAST Search History**EAST Search History (Prior Art)**

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L3	2558	(substrate wafer semiconductor) with (clean \$3 rins\$3 treat\$3 process \$3) and (transfer\$3 carry \$3 transport\$3) near4 (contamination)	US-PGPUB; USPAT	OR	ON	2010/09/08 17:55
S1	746	(substrate wafer semiconductor) with (multi many multiple plurality) near3 (tier stage level) and (transfer handl \$3) with (robot)	US-PGPUB; USPAT	OR	ON	2010/03/24 14:13
S2	63	(substrate wafer semiconductor) with (multi many multiple plurality) near3 (tier stage level) and (transfer handl \$3) with (robot) and (clean \$3 rins\$3 process\$3 treat \$3 wash\$3) near3 (bath)	US-PGPUB; USPAT	OR	ON	2010/03/24 14:14
S3	3	(substrate wafer semiconductor) with (stack \$3) near3 (chambers baths) and (clean\$3 rins \$3) with (bath) with (overflow\$3)	US-PGPUB; USPAT	OR	ON	2010/03/24 14:47
S4	782	(substrate wafer semiconductor) with (stack \$3) near3 (chambers baths)	US-PGPUB; USPAT	OR	ON	2010/03/24 14:48
S5	10	(substrate wafer semiconductor) with (stack \$3) near3 (chambers baths) and (wash\$3 rins \$3 clean\$3) near3 (bath)	US-PGPUB; USPAT	OR	ON	2010/03/24 14:48
S6	1	"10574113"	US-PGPUB; USPAT	OR	ON	2010/03/24 15:02
S7	1	("6478035").PN.	US-PGPUB; USPAT	OR	ON	2010/03/24 15:04

S8	3740	(substrate wafer semiconductor) with (clean \$3 rins\$3 treat\$3 process \$3) and (clean\$3 rins\$3 treat\$3 process\$3) adj ("baths")	US-PGPUB; USPAT	OR	ON	2010/03/24 17:33
S9	11	(substrate wafer semiconductor) with (clean \$3 rins\$3 treat\$3 process \$3) and (clean\$3 rins\$3 treat\$3 process\$3) adj ("baths") with (plurality) with (chamber)	US-PGPUB; USPAT	OR	ON	2010/03/24 17:33
S10	72	(substrate wafer semiconductor) with (clean \$3 rins\$3 treat\$3 process \$3) and transfer adj bath	US-PGPUB; USPAT	OR	ON	2010/03/24 17:40
S11	1882	(substrate wafer semiconductor) with (clean \$3 rins\$3 treat\$3 process \$3) and (transfer\$3 carry \$3 transport\$3) near3 (bath)	US-PGPUB; USPAT	OR	ON	2010/03/24 18:31
S12	254	(substrate wafer semiconductor) with (clean \$3 rins\$3 treat\$3 process \$3) and (transfer\$3 carry \$3 transport\$3) adj (bath)	US-PGPUB; USPAT	OR	ON	2010/03/24 18:31
S13	2474	(substrate wafer semiconductor) with (clean \$3 rins\$3 treat\$3 process \$3) and (transfer\$3 carry \$3 transport\$3) near4 (contamination)	US-PGPUB; USPAT	OR	ON	2010/03/25 16:14
S14	423	(substrate wafer semiconductor) with (clean \$3 rins\$3 treat\$3 process \$3) and (transfer\$3 carry \$3 transport\$3) near4 (contamination) near3 (prevent\$3)	US-PGPUB; USPAT	OR	ON	2010/03/25 16:14
S15	187	(substrate wafer semiconductor) with (clean \$3 rins\$3 treat\$3 process \$3) same (transfer\$3 carry \$3 transport\$3) near4 (contamination) near3 (prevent\$3)	US-PGPUB; USPAT	OR	ON	2010/03/25 16:15

S16	7	(substrate wafer semiconductor) with (clean\$3 rins\$3 treat\$3 process\$3) and (transfer\$3 carry\$3 transport\$3) near2 (robot) near4 (contamination) near3 (prevent\$3)	US-PGPUB; USPAT	OR	ON	2010/03/25 16:19
S17	1	(substrate wafer semiconductor) with (clean\$3 rins\$3 treat\$3 process\$3) and (transfer\$3 carry\$3 transport\$3) near2 (robot) near5 (plurality two multiple) with (contamination) near3 (prevent\$3)	US-PGPUB; USPAT	OR	ON	2010/03/25 16:19
S18	5271	(substrate wafer semiconductor) with (clean\$3 rins\$3 treat\$3 process\$3) and (transfer\$3 carry\$3 transport\$3) with (exhaust fan blower)	US-PGPUB; USPAT	OR	ON	2010/03/25 16:25
S19	221	(substrate wafer semiconductor) with (clean\$3 rins\$3 treat\$3 process\$3) and (transfer\$3 carry\$3 transport\$3) near3 (robot support) with (exhaust fan blower)	US-PGPUB; USPAT	OR	ON	2010/03/25 16:25
S20	8	(substrate wafer semiconductor) with (clean\$3 rins\$3 treat\$3 process\$3) and (clean\$3) adj (bath) with exhaust with filter	US-PGPUB; USPAT	OR	ON	2010/03/25 16:45
S21	327	(substrate wafer semiconductor) with (clean\$3 rins\$3 treat\$3 process\$3) and (clean\$3) near3 (transfer\$3 carry\$3 transport\$3) near3 (bath tank)	US-PGPUB; USPAT	OR	ON	2010/03/25 17:09
S22	206	(clean\$3) with (substrate wafer) near3 (transfer\$3 carry\$3 transport\$3) near3 (bath tank)	US-PGPUB; USPAT	OR	ON	2010/03/25 17:09

S23	86	(clean\$3) with (substrate wafer) and ("transport bath" "transport tank" "transfer bath" "transfer tank" "carrier bath" "carrier tank")	US-PGPUB; USPAT	OR	ON	2010/03/25 18:07
S24	2	("2003/0079500").URPN.	USPAT	OR	ON	2010/03/25 18:16
S25	14	(substrate wafer) near3 (submer\$6 immer\$5) with (carry\$3 transport\$3 transfer) with (deionized)	US-PGPUB; USPAT	OR	ON	2010/03/25 18:26
S26	2	"7520287"	US-PGPUB; USPAT	OR	ON	2010/03/27 14:10
S27	4	"2000026080"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2010/03/27 14:12
S28	3	"07194969"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2010/03/27 14:14
S29	12	"3438316"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2010/03/27 14:14
S30	2	"60091300"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2010/03/27 14:17
S31	0	10/574113	USPAT	OR	ON	2010/03/27 14:36
S32	1	10/574113	US-PGPUB; USPAT	OR	ON	2010/03/27 14:36
S33	5912	spring adj valve	US-PGPUB; USPAT	OR	ON	2010/03/27 14:53
S34	313	spring adj valve with (plate and spring)	US-PGPUB; USPAT	OR	ON	2010/03/27 15:05
S35	1	spring adj valve with (plate and spring) and (switch with rod)	US-PGPUB; USPAT	OR	ON	2010/03/27 15:05
S36	313	spring adj valve with (plate and spring)	US-PGPUB; USPAT	OR	ON	2010/03/27 15:06
S37	572	switch with dry\$3 with valve	US-PGPUB; USPAT	OR	ON	2010/03/27 15:26
S38	159	switch with dry\$3 with valve same gas	US-PGPUB; USPAT	OR	ON	2010/03/27 15:27
S39	2318	substrate with (clean\$3 process\$3 rins\$3 treat\$3) and (load unload) with (align\$4)	US-PGPUB; USPAT	OR	ON	2010/03/27 15:34

S40	105	substrate with (clean\$3 process\$3 rins\$3 treat\$3) and (load unload) with (align\$4) with (vertical or horizontal)	US-PGPUB; USPAT	OR	ON	2010/03/27 15:34
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